Francis Maury

List of Publications by Year
in descending order

126	2,069	236925 25	315739 38
papers	citations	h-index	g-index

127	127	127	1836
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Synthesis, characterization and photocatalytic activity of TiO2 supported natural palygorskite microfibers. Applied Clay Science, 2011, 52, 301-311.	5.2	107
2	A review of additive manufacturing of ceramics by powder bed selective laser processing (sintering /) Tj ETQq0 0 0 rgBT /Overlock 10 Tf 2021, 5, 100073.	2.0	67
3	Various chemical mechanisms for the crystal growth of IIIâ€“V semiconductors using coordination compounds as starting material in the MOCVD process. Journal of Crystal Growth, 1981, 55, 135-144.	1.5	59
4	DLI-CVD of TiO2â€“Cu antibacterial thin films: Growth and characterization. Surface and Coatings Technology, 2009, 204, 887-892.	4.8	56
5	Real time monitoring of the growth of metallic thin films by in situ pyrometry. European Physical Journal Special Topics, 2002, 12, 9-8.	0.2	56
6	Crystal structure and magnetism of sodium bis(oxalato)cuprate(II)dihydrate, Na2Cu(C2O4)2.2H2O. A deductive proposal for the structure of copper oxalate, CuC2O4.xH2O (O .ltoreq. .times. .ltoreq. 1). Inorganic Chemistry, 1980, 19, 2074-2078.	4.0	55
7	Characterization of chromium nitride and carbonitride coatings deposited at low temperature by organometallic chemical vapour deposition. Surface and Coatings Technology, 1991, 46, 275-288.	4.8	49
8	Trends in precursor selection for MOCVD. Chemical Vapor Deposition, 1996, 2, 113-116.	1.3	49
9	Atmospheric pressure MOCVD of TiO2 thin films using various reactive gas mixtures. Surface and Coatings Technology, 2004, 188-189, 255-259.	4.8	49
10	CVD Elaboration of Nanostructured TiO₂â€Ag Thin Films with Efficient Antibacterial Properties. Chemical Vapor Deposition, 2010, 16, 35-41.	1.3	45
11	Visible Thermochromism in Vanadium Pentoxide Coatings. ACS Applied Materials & Interfaces, 2017, 9, 21447-21456.	8.0	45
12	Elucidating the crystal-chemistry of Jbel Rhassoul stevensite (Morocco) by advanced analytical techniques. Clay Minerals, 2008, 43, 393-403.	0.6	43
13	Microfibrous TiO2 supported photocatalysts prepared by metal-organic chemical vapor infiltration for indoor air and waste water purification. Applied Catalysis B: Environmental, 2009, 91, 225-233.	20.2	43
14	Growth of TiO2 thin films by AP-MOCVD on stainless steel substrates for photocatalytic applications. Surface and Coatings Technology, 2007, 201, 9304-9308.	4.8	42
15	N-doped TiO2 coatings grown by atmospheric pressure MOCVD for visible light-induced photocatalytic activity. Surface and Coatings Technology, 2007, 201, 9349-9353.	4.8	42
16	Chemical vapor deposition of SnO2 coatings on Ti plates for the preparation of electrocatalytic anodes. Surface and Coatings Technology, 2002, 151-152, 9-13.	4.8	41
17	Iridium coatings grown by metalâ€“organic chemical vapor deposition in a hot-wall CVD reactor. Surface and Coatings Technology, 2003, 163-164, 208-213.	4.8	41
18	Comprehensive physicochemical study of dioctahedral palygorskite-rich clay from Marrakech High Atlas (Morocco). Physics and Chemistry of Minerals, 2013, 40, 411-424.	0.8	41

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19	Synthesis and characterization of diethylphosphino Ga(III) and In(III) complexes with covalent metal-phosphorus bonds. Polyhedron, 1984, 3, 581-584.	2.2	40
20	Organometallic molecular precursors for low-temperature MOCVD of III-V semiconductors. Advanced Materials, 1991, 3, 542-548.	21.0	39
21	Chemical vapor deposition and characterization of nitrogen doped TiO2 thin films on glass substrates. Thin Solid Films, 2009, 518, 1299-1303.	1.8	33
22	TiOxNy coatings grown by atmospheric pressure metal organic chemical vapor deposition. Surface and Coatings Technology, 2010, 205, 1287-1293.	4.8	33
23	Al2O3 coatings on stainless steel from Al metal-organic chemical vapor deposition and thermal treatments. Surface and Coatings Technology, 2000, 125, 419-423.	4.8	32
24	Investigation of [(py) (Et) Co(dmg Â· GaEt2)2] and [Ni(dmg Â· GaEt2)2] (py = pyridine; dmg =) Tj ETQq0 0 0 rgBT /Overlock 10 Tf 50 54 structure of [(py)(Et)Co(dmg Â· GaEt2)(dmgH)]. Journal of Organometallic Chemistry, 1994, 472, 317-328.	1.8	30
25	Correlation between eletrokinetic mobility and ionic dyes adsorption of Moroccan stevensite. Applied Clay Science, 2010, 48, 527-530.	5.2	28
26	MOVPE of GaAs from the new adducts [ClR2Ga Â· AsEt2]2CH2 (R = Me, Et) and (C6F5)3 â^' n MenGa Â· AsEt3 (n) Tj ETQq0 0 0 rgBT /Ov	1.5	25
27	Influence of organochromium precursor chemistry on the microstructure of MOCVD chromium carbide coatings. Surface and Coatings Technology, 1990, 43-44, 185-198.	4.8	25
28	Evaluation of tetra-alkylchromium precursors for organometallic chemical vapour deposition I. films grown using Cr[CH2C(CH3)3]4. Thin Solid Films, 1992, 207, 82-89.	1.8	25
29	Study of CoGa deposition from the single source precursor (CO)4CoGaCl2 (THF). Journal of Organometallic Chemistry, 1993, 449, 159-165.	1.8	25
30	Structural characterization of chromium carbide coatings deposited at low temperature by low pressure chemical vapour decomposition using dicumene chromium. Surface and Coatings Technology, 1990, 41, 51-61.	4.8	24
31	Antibacterial properties of TiO2â€“Cu composite thin films grown by a one step DLICVD process. Surface and Coatings Technology, 2014, 242, 187-194.	4.8	24
32	Vapor phase surface functionalization under ultra violet activation of parylene thin films grown by chemical vapor deposition. Thin Solid Films, 2010, 518, 1675-1681.	1.8	23
33	Physicochemical Study of Photocatalytic Activity of TiO₂Supported Palygorskite Clay Mineral. International Journal of Photoenergy, 2013, 2013, 1-6.	2.5	23
34	Epitaxial growth of cobalt-gallium on gallium arsenide by organometallic chemical vapor deposition. Chemistry of Materials, 1993, 5, 84-89.	6.7	22
35	Selection of metalorganic precursors for MOCVD of metallurgical coatings: application to Cr-based coatings. Surface and Coatings Technology, 1996, 86-87, 316-324.	4.8	22
36	A miniaturised silicon based enzymatic biosensor: towards a generic structure and technology for multi-analytes assays. Sensors and Actuators B: Chemical, 2002, 82, 227-232.	7.8	20

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37	Pyrosol deposition of anatase TiO2 thin films starting from Ti(OiPr)4/acetylacetone solutions. Thin Solid Films, 2007, 515, 7732-7739.	1.8	20
38	Multilayer chromium based coatings grown by atmospheric pressure direct liquid injection CVD. Surface and Coatings Technology, 2009, 204, 983-987.	4.8	20
39	Tunable thermochromic properties of V 2 O 5 coatings. Materials Today Physics, 2017, 2, 1-5.	6.0	20
40	A Thermodynamic Approach to the CVD of Chromium and of Chromium Carbides Starting from Cr(C6H6)2. Chemical Vapor Deposition, 1998, 04, 69-76.	1.3	20
41	Chromium Carbide Growth by Direct Liquid Injection Chemical Vapor Deposition in Long and Narrow Tubes, Experiments, Modeling and Simulation. Coatings, 2018, 8, 220.	2.6	18
42	Orbital interactions in a strongly antiferromagnetically coupled copper(II) linear chain: CuSe2O5. Solid State Communications, 1980, 34, 971-975.	1.9	17
43	Optimization of the Vaporization of Liquid and Solid CVD Precursors: Experimental and Modeling Approaches. Chemical Vapor Deposition, 2007, 13, 638-643.	1.3	16
44	Croissance Ã©pitaxique de GaAs1â^'xPx (0 < x < 0.6) par OM-CVD Ã¡ partir du complexe ClEt2GaÂ·AsEt3 et de la diethyl phosphine: une source de phosphore originale HPEt2. Journal of Crystal Growth, 1983, 62, 568-576.	1.5	15
45	Evaluation of tetra-alkylchromium precursors for organometallic chemical vapor deposition II: Unusual low temperature chromium carbide deposition from Cr[C(CH3)3]4. Thin Solid Films, 1992, 219, 24-29.	1.8	14
46	Evidence for a Cr metastable phase as a tracer in DLI-MOCVD chromium hard coatings usable in high temperature environment. Applied Surface Science, 2017, 422, 198-206.	6.1	14
47	Control of the uniformity of thickness of Ni thin films deposited by low pressure chemical vapor deposition. Surface and Coatings Technology, 1994, 64, 21-27.	4.8	13
48	Thermal decomposition mechanisms of tetraethylgermane in metal-organic chemical vapor deposition. Journal of Analytical and Applied Pyrolysis, 1998, 44, 153-165.	5.5	13
49	Experimental and numerical study for direct powder bed selective laser processing (sintering/melting) of silicon carbide ceramic. Materials Research Express, 2021, 8, 045603.	1.6	13
50	Mass spectrometric study of the pyrolysis of organometallic precursors usable in GaAs vapor phase epitaxy. Journal of Crystal Growth, 1988, 91, 105-110.	1.5	12
51	Organo-metallic chemical vapour deposition of silicon-rich amorphous SixC1â^'x refractory layers using SiEt4 as a single source. Materials Science & Engineering A: Structural Materials: Properties, Microstructure and Processing, 1989, 109, 69-75.	5.6	12
52	Thermal decomposition of V(NEt2)4 in an MOCVD reactor: a low-temperature route to vanadium carbonitride coatings. Journal of Materials Chemistry, 1996, 6, 1501.	6.7	12
53	A Thermodynamic Approach to the CVD of Chromium and of Chromium Carbides Starting from Cr(C6H6)2. Chemical Vapor Deposition, 1998, 4, 69-76.	1.3	12
54	Gas and plasma nitriding pretreatments of steel substrates before CVD growth of hard refractory coatings. Thin Solid Films, 1998, 315, 179-185.	1.8	12

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55	Low Temperature Metallorganic Chemical Vapor Deposition Routes to Chromium Metal Thin Films Using Bis(benzene)chromium. Journal of the Electrochemical Society, 1999, 146, 3716-3723.	2.9	12
56	SnO2 coated Ni particles prepared by fluidized bed chemical vapor deposition. Surface and Coatings Technology, 2006, 200, 6733-6739.	4.8	12
57	Nanocrystalline chromium-based coatings deposited by DLI-MOCVD under atmospheric pressure from Cr(CO)6. Surface and Coatings Technology, 2006, 200, 6267-6271.	4.8	12
58	Densification of surface-modified silicon carbide powder by spark-plasma-sintering. Journal of the European Ceramic Society, 2021, 41, 7543-7551.	5.7	12
59	Chromium-based coatings by atmospheric chemical vapor deposition at low temperature from Cr(CO)6. Surface and Coatings Technology, 2005, 200, 1407-1412.	4.8	11
60	Chemical Vapor Deposition of TiO₂ for Photocatalytic Applications and Biocidal Surfaces. Key Engineering Materials, 2009, 415, 1-4.	0.4	11
61	Synthesis and crystal structures of lithium and of sodium bis(dithioxalato)nickelate(II). Comparison with the potassium derivatives. Inorganica Chimica Acta, 1980, 41, 185-194.	2.4	10
62	Co-pyrolysis of hydrocarbons and SiEt4for the synthesis of graduated SixC1â€“xceramic thin films by chemical vapour deposition. Journal of Materials Chemistry, 1994, 4, 695-701.	6.7	10
63	Low-temperature MOCVD of Vâ€“Câ€“N coatings using bis(arene)vanadium as precursors. Surface and Coatings Technology, 1998, 108-109, 200-205.	4.8	10
64	Iron Thin Films from Fe(CO)[sub 5] and FeCp[sub 2]â•H[sub 2]O under Atmospheric Pressure. Journal of the Electrochemical Society, 2006, 153, G1025.	2.9	10
65	Chemical vapor infiltration of photocatalytically active TiO2 thin films on glass microfibers. Surface and Coatings Technology, 2007, 201, 9354-9358.	4.8	10
66	Thermodynamic simulation of atmospheric DLI-CVD processes for the growth of chromium-based hard coatings using bis(benzene)chromium as molecular source. Surface and Coatings Technology, 2008, 203, 516-520.	4.8	10
67	Raman scattering analysis of disorder in heterogeneous (GaAs)1â”x(SiC2:H)x films grown by metal-organic chemical vapour deposition. Thin Solid Films, 1987, 155, 331-342.	1.8	9
68	Mass spectrometric study of the pyrolysis of organometallic precursors usable in GaAs vapor phase epitaxy. Journal of Crystal Growth, 1988, 91, 97-104.	1.5	9
69	Photo-MOCVD of copper thin films using Cu(II) and Cu(I) precursors for low-temperature metallization. Advanced Materials for Optics and Electronics, 2000, 10, 123-133.	0.4	9
70	Embedded layer of Ag nanoparticles prepared by a combined PECVD/PVD process producing SiOxCyâ€“Ag nanocomposite thin films. Nanotechnology, 2012, 23, 015603.	2.6	9
71	Scanning Strategy Investigation for Direct Powder Bed Selective Laser Processing of Silicon Carbide Ceramic. Applied Sciences (Switzerland), 2022, 12, 788.	2.5	9
72	Organochromium precursors for low-temperature OMCVD of chromium-based coatings. Applied Organometallic Chemistry, 1992, 6, 619-626.	3.5	8

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73	GaAs growth by photon-assisted metalorganic molecular beam epitaxy using ethyl derivatives of gallium and arsenic. Applied Surface Science, 1995, 86, 447-452.	6.1	8
74	MOCVD Route to Chromium Carbonitride Thin Films Using Cr(NEt2)4 as Single-Source Precursor: Growth and Mechanism. Chemical Vapor Deposition, 1997, 3, 137-143.	1.3	8
75	Making of specific electrodes by CVD. Surface and Coatings Technology, 1998, 100-101, 169-172.	4.8	8
76	Photo-assisted MOCVD of copper using Cu(hfa)(COD) as precursor. Applied Surface Science, 2000, 168, 57-60.	6.1	8
77	Non-hydrothermal synthesis and structure determination of two new Î²-octamolybdate (VI) stabilized with dialkylammonium counterions. Journal of Molecular Structure, 2018, 1170, 44-50.	3.6	8
78	Some investigations on the chemisorption and thermal heterogeneous decomposition of the MOCVD adduct ClMe2GaAsEt3. Journal of Crystal Growth, 1986, 78, 185-188.	1.5	7
79	Chemical and structural characterizations of chemical vapour deposited SixC1â˜'x films. Materials Letters, 1991, 11, 257-260.	2.6	7
80	Organometallic vapor phase epitaxy of CoGa on (100)GaAs. Applied Physics Letters, 1992, 61, 1075-1077.	3.3	7
81	MOCVD of hard metallurgical coatings: Examples in the Crâ€"Câ€"N system. Electrochimica Acta, 2005, 50, 4525-4530.	5.2	7
82	Diagnostic in TCOs CVD processes by IR pyrometry. Thin Solid Films, 2007, 515, 8619-8623.	1.8	7
83	Metal-organic chemical vapour codeposition of GaAs and SixC1â˜'x groups: Growth of a new amorphous semiconductor. Thin Solid Films, 1984, 117, 299-309.	1.8	6
84	Residual stresses analyses of metallo-organic chemically vapour-deposited Cr7C3 coatings on SAE 4135 steel substrates. Surface and Coatings Technology, 1991, 45, 185-192.	4.8	6
85	Low-temperature MOCVD of chromium carbonitride coatings from tetrakis(diethylamido)chromium and pyrolysis mechanism of this single-source precursor. Applied Organometallic Chemistry, 1998, 12, 189-199.	3.5	6
86	Light modulation in phase change disordered metamaterial - A smart cermet concept. Materials Today Physics, 2017, 3, 41-47.	6.0	6
87	Threshold photoemission analysis of the surface reactions of triethylgallium and trimethylgallium on GaAs(100): A promising technique for kinetics studies. Applied Physics Letters, 1999, 74, 266-268.	3.3	5
88	Single-phased hard coatings of the metastable Cr3(C0.8N0.2)2 ternary phase grown by low pressure MOCVD. Surface and Coatings Technology, 2000, 133-134, 198-202.	4.8	5
89	In-Situ Optical Pyrometry in the CVD of Metallic Thin Films for Real Time Control of the Growth. Chemical Vapor Deposition, 2003, 9, 34-39.	1.3	5
90	One pot-synthesis of the fourth category of dinuclear molybdenum(VI) oxalate series: Structure and study of thermal and redox properties. Inorganica Chimica Acta, 2019, 491, 84-92.	2.4	5

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91	Pyrolysis of various organosilazanes used as single precursor of SiNxCy:H films OMCVD process. Journal of Analytical and Applied Pyrolysis, 1989, 17, 67-81.	5.5	4
92	Chemical vapour infiltration of SixC1â^'x films for the preparation of composite materials using both organosilicon and hydrocarbon precursors. Thin Solid Films, 1992, 209, 52-58.	1.8	4
93	Metalorganic chemical vapor deposition of sno thin films using tetraethyltin: Growth and characterization. Annales De Chimie: Science Des Materiaux, 1998, 23, 355-358.	0.4	4
94	Comparative Study of Antibacterial Efficiency of M-TiO₂ (M = Ag, Cu) Thin Films Grown by CVD. Key Engineering Materials, 0, 617, 127-130.	0.4	4
95	Process parameters investigation for direct powder bed selective laser processing of silicon carbide parts. Progress in Additive Manufacturing, 2022, 7, 1307-1322.	4.8	4
96	Optical and electrical properties of the disordered composite semiconductor (GaAs)‹sub›1â^'x‹/sub› (SiC‹sub›2‹/sub› : H)‹sub›x‹/sub›, grown by metal-organic chemical vapour deposition. The Philosophical Magazine: Physics of Condensed Matter B, Statistical Mechanics, Electronic, Optical and Magnetic Properties, 1986, 53, 445-457.	0.6	3
97	Chemical vapor deposition of ge thin films using geet: study of the reaction mechanisms. Annales De Chimie: Science Des Materiaux, 1998, 23, 381-384.	0.4	3
98	DÃ©pÃ´t chimique en phase vapeur Ã basse tempÃ©rature de revÃªtements dans le systÃ¨me V-C-N Ã partir de bis(arene)vanadium. Annales De Chimie: Science Des Materiaux, 1998, 23, 695-706.	0.4	3
99	Chemical vapor deposition of tin oxide from SnEt4. European Physical Journal Special Topics, 1999, 09, Pr8-651-Pr8-657.	0.2	3
100	In situ IR pyrometric analysis during thermal treatment in air of TiOxNy coatings. Surface and Coatings Technology, 2008, 202, 2423-2427.	4.8	3
101	Evidences for liquid encapsulation in PMMA ultra-thin film grown by liquid injection Photo-CVD. Progress in Organic Coatings, 2013, 76, 1846-1850.	3.9	3
102	Two new inorganicâ€“organic hybrid materials based on Î²- and Î³-octamolybdate clusters: Synthesis, structure determination and solid-state photochromic properties. Polyhedron, 2021, 194, 114919.	2.2	3
103	Assessment of tetra-alkylchromium compounds for low temperature organo-metallic chemical vapour deposition of Cr-based coatings. Surface and Coatings Technology, 1992, 54-55, 204-210.	4.8	3
104	Structural characterizations of MOCVD (GaAs)1â^'x(SiC2H)x films: Evidence for a multiphase structure. Materials Letters, 1986, 4, 249-255.	2.6	2
105	Chemical beam epitaxy of CoGa on GaAs using GaEt3 and CpCo(CO)2 as dual organometallic sources. Microelectronic Engineering, 1997, 37-38, 165-171.	2.4	2
106	MÃ©canisme de dÃ©composition des composÃ©s M(NEt) (M = V, Cr) lors de leur utilisation comme mono-source pour la croissance de films M-C-N par MOCVD. Annales De Chimie: Science Des Materiaux, 1998, 23, 667-679.	0.4	2
107	PrÃ©traitements de nitruration compatibles avec les procÃ©dÃ©s MOCVD et PACVD: Influence sur l'adhÃ©rence de revÃªtements cÃ©ramiques sur ACIER. Annales De Chimie: Science Des Materiaux, 1998, 23, 707-720.	0.4	2
108	MOCVD of Cr[sub 3](C,N)[sub 2] and CrSi[sub x]C[sub y] Films. Journal of the Electrochemical Society, 2005, 152, G907.	2.9	2

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109	Thermally Induced Release of Internal Liquid Phase Encapsulated in a Polymer Membrane Grown by Photoactivated DLICVD. Chemical Vapor Deposition, 2012, 18, 274-281.	1.3	2
110	Optical and morphological properties of thermochromic V 2 O 5 coatings. Data in Brief, 2017, 14, 348-353.	1.0	2
111	Low temperature Direct Liquid Injection MOCVD of amorphous CrCx coatings in large-scale reactors: An original route to nanostructured multilayer coatings. Surface and Coatings Technology, 2021, 416, 127174.	4.8	2
112	Driving Force for Free-Carbon Incorporation in Chromium Carbide Films Processed by MOCVD. Chemical Vapor Deposition, 1998, 04, 96-99.	1.3	2
113	Mass Spectrometric Study of the Gas Phase During Chemical Vapor Deposition of Pyrolytic Carbon. European Physical Journal Special Topics, 1995, 05, C5-89-C5-96.	0.2	2
114	A.c. properties of polycrystalline GaAs and (GaAs)1â^'x(SiC2:H)x grown by metal-organic chemical vapour deposition. Thin Solid Films, 1987, 146, 241-254.	1.8	1
115	PrÃ©curseurs mÃ©tallorganiques pour le dÃ©pÃ´t chimique Ã partir dune phase gazeuse de revÃªtements dans le systÃ¨me Ti-V-C-N. Annales De Chimie: Science Des Materiaux, 1998, 23, 637-653.	0.4	1
116	Driving Force for Free-Carbon Incorporation in Chromium Carbide Films Processed by MOCVD. Chemical Vapor Deposition, 1998, 4, 96-99.	1.3	1
117	MOCVD of Cr[sub 3](C,N)[sub 2] and CrSi[sub x]C[sub y] Films. Journal of the Electrochemical Society, 2005, 152, G651.	2.9	1
118	Diagnostic in CVD processes by IR pyrometry. Chemical Engineering and Processing: Process Intensification, 2008, 47, 383-389.	3.6	1
119	A new good thermal stability hybrid material based on heptamolybdate cluster: Synthesis and structural characterization. Chemical Data Collections, 2020, 30, 100576.	2.3	1
120	Photo-MOCVD of Cu thin films using Cu(hfa)(MHY) as precursor. European Physical Journal Special Topics, 1999, 09, Pr8-791-Pr8-798.	0.2	1
121	DÃ©pÃ´t de Cr Ã basse tempÃ©rature par MOCVD: inhibition de l'incorporation du carbone. Annales De Chimie: Science Des Materiaux, 1998, 23, 681-693.	0.4	0
122	Study of the properties of in situ Pt-doped SnO2 thin films prepared by metal-organic chemical vapour deposition. Annales De Chimie: Science Des Materiaux, 2002, 27, 61-68.	0.4	0
123	Chemical Vapor Deposition of Cr-Based Thin Films as Diffusion Barriers in Copper Metallization. Materials Science Forum, 2003, 426-432, 3439-3444.	0.3	0
124	In Recognition of Professor Hitchman: Advances in Chemical Vapor Deposition. Advanced Materials Interfaces, 2017, 4, 1700984.	3.7	0
125	MOCVD and properties of in situ doped Pt-SnO₂ thin films. European Physical Journal Special Topics, 1999, 09, Pr8-643-Pr8-650.	0.2	0
126	EVIDENCE FOR FREE CARBON IN AMORPHOUS OMCVD SILICON-RICH Si_xC_{1-x} COATINGS. Journal De Physique Colloque, 1989, 50, C5-765-C5-772.	0.2	0